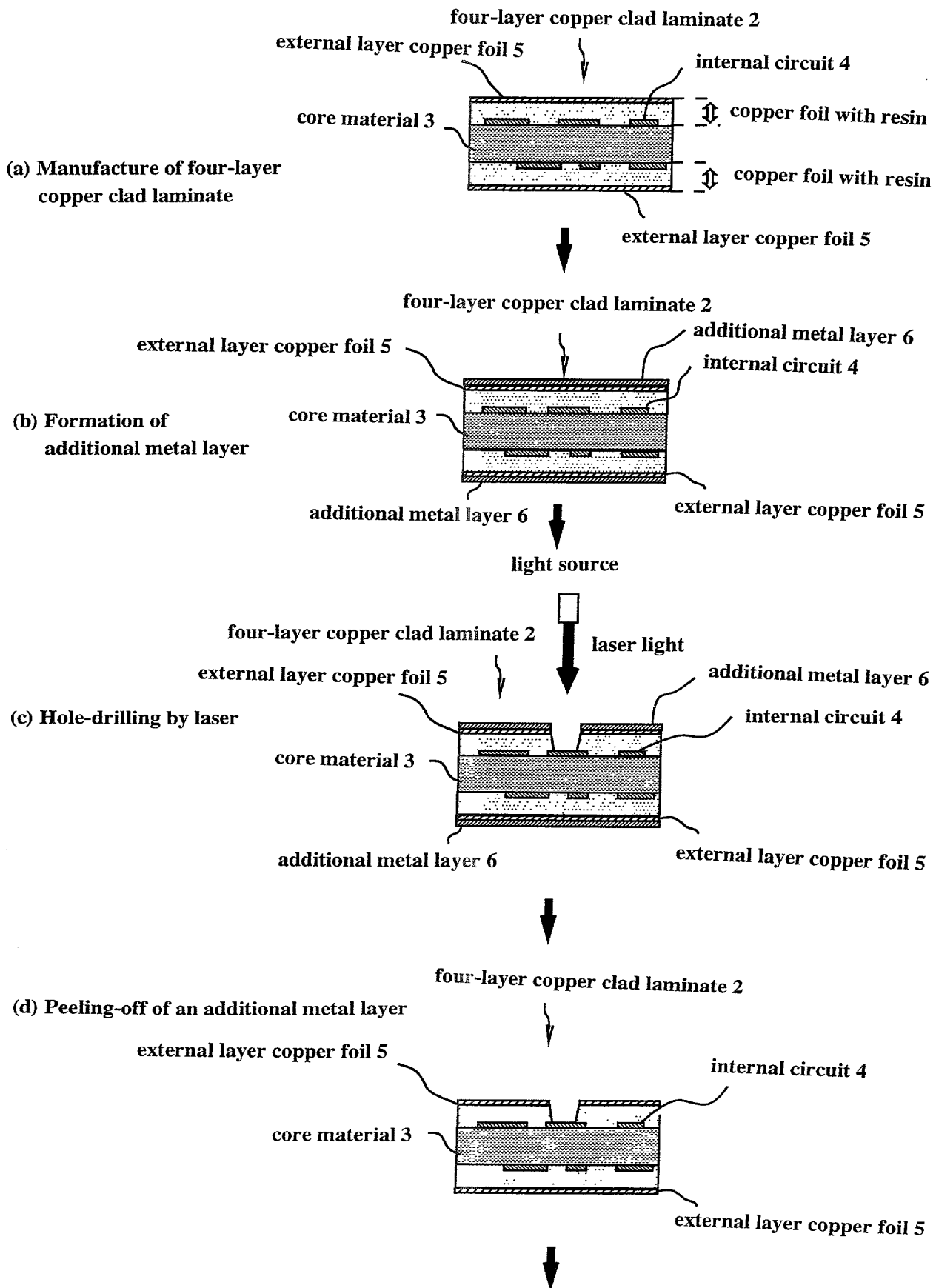
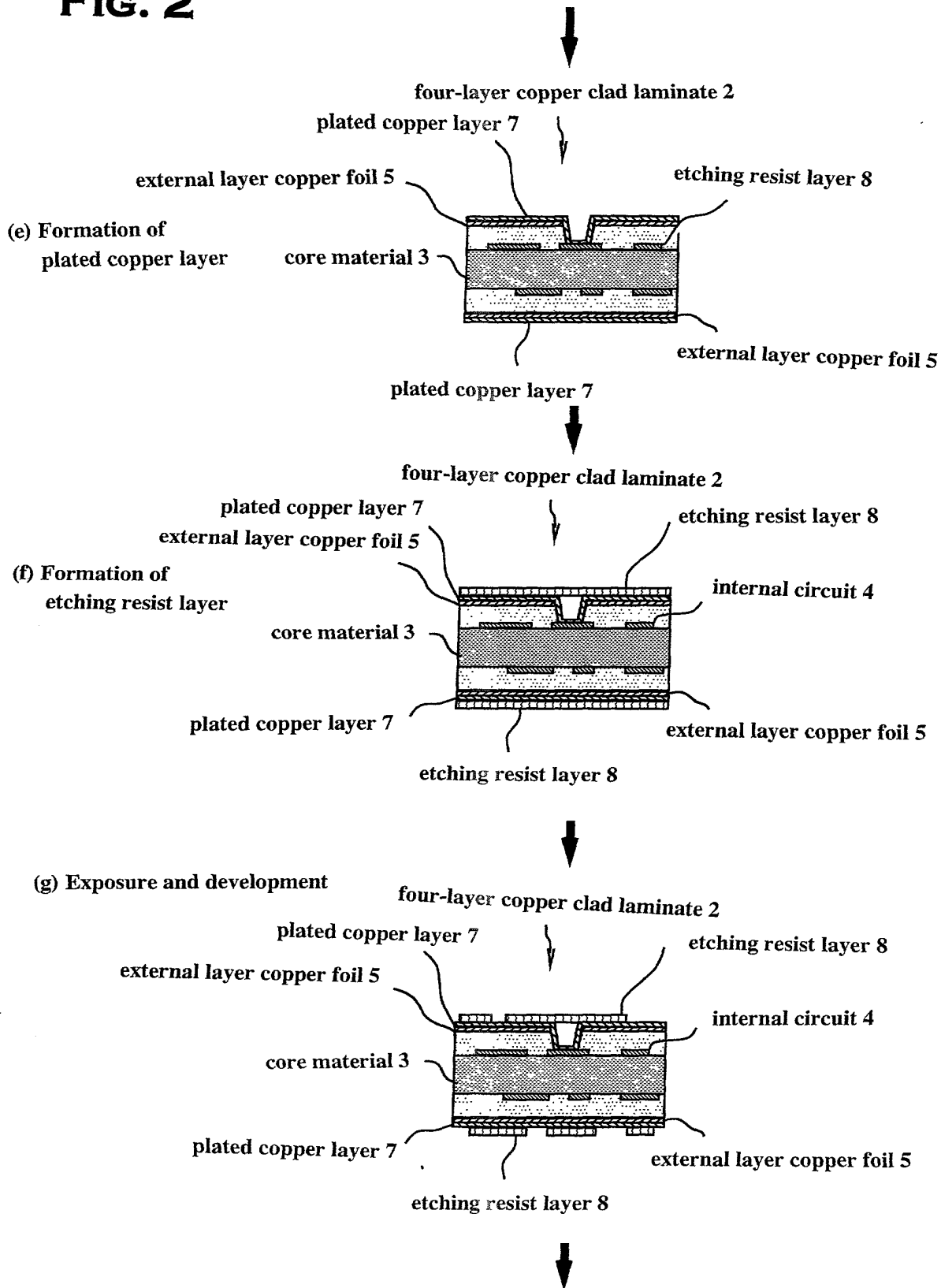


**FIG. 1**



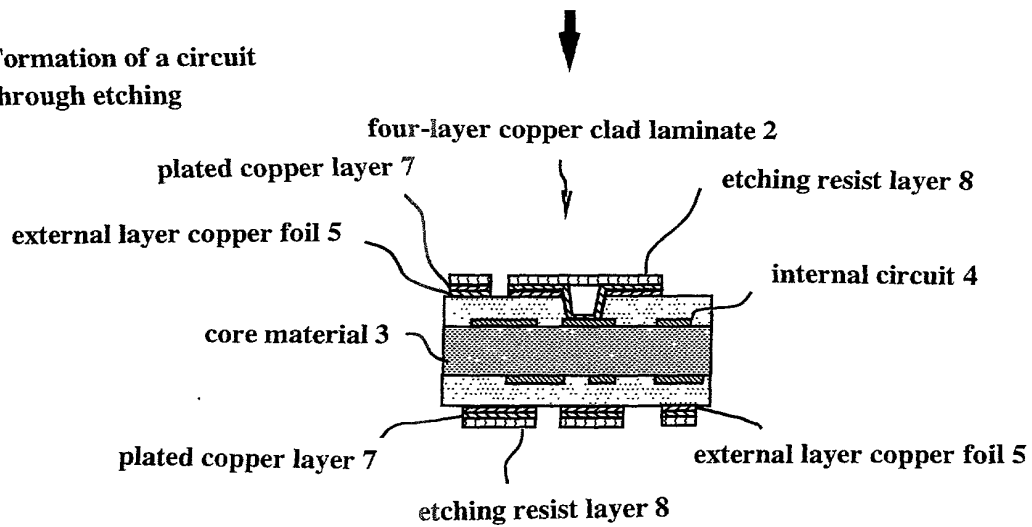
4002154-02600

**FIG. 2**

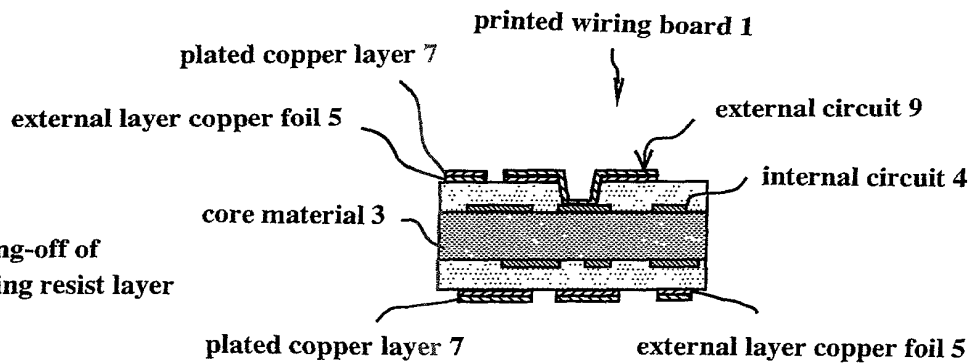


**FIG. 3**

(h) Formation of a circuit through etching



(i) Peeling-off of etching resist layer



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FIG. 4

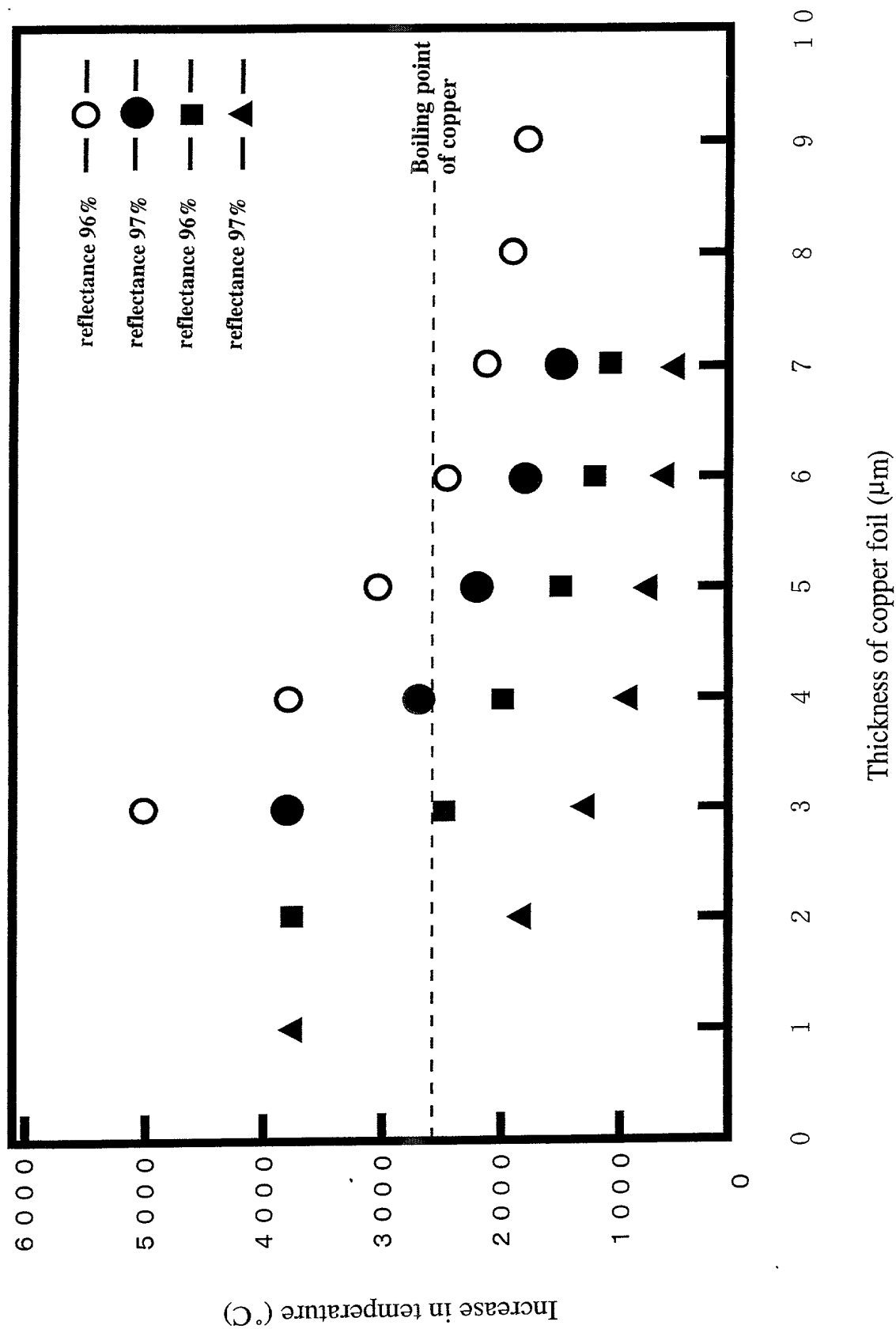
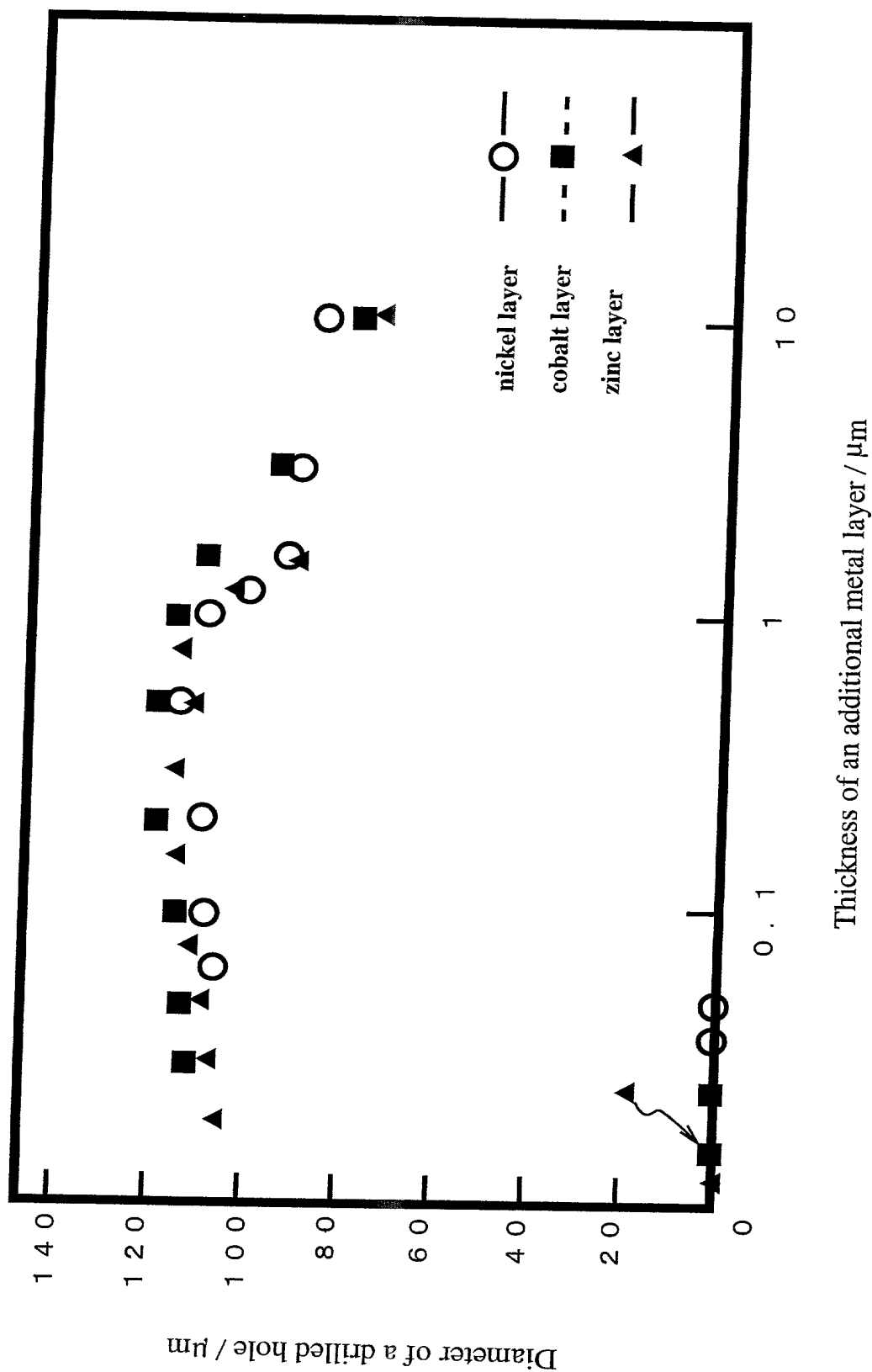
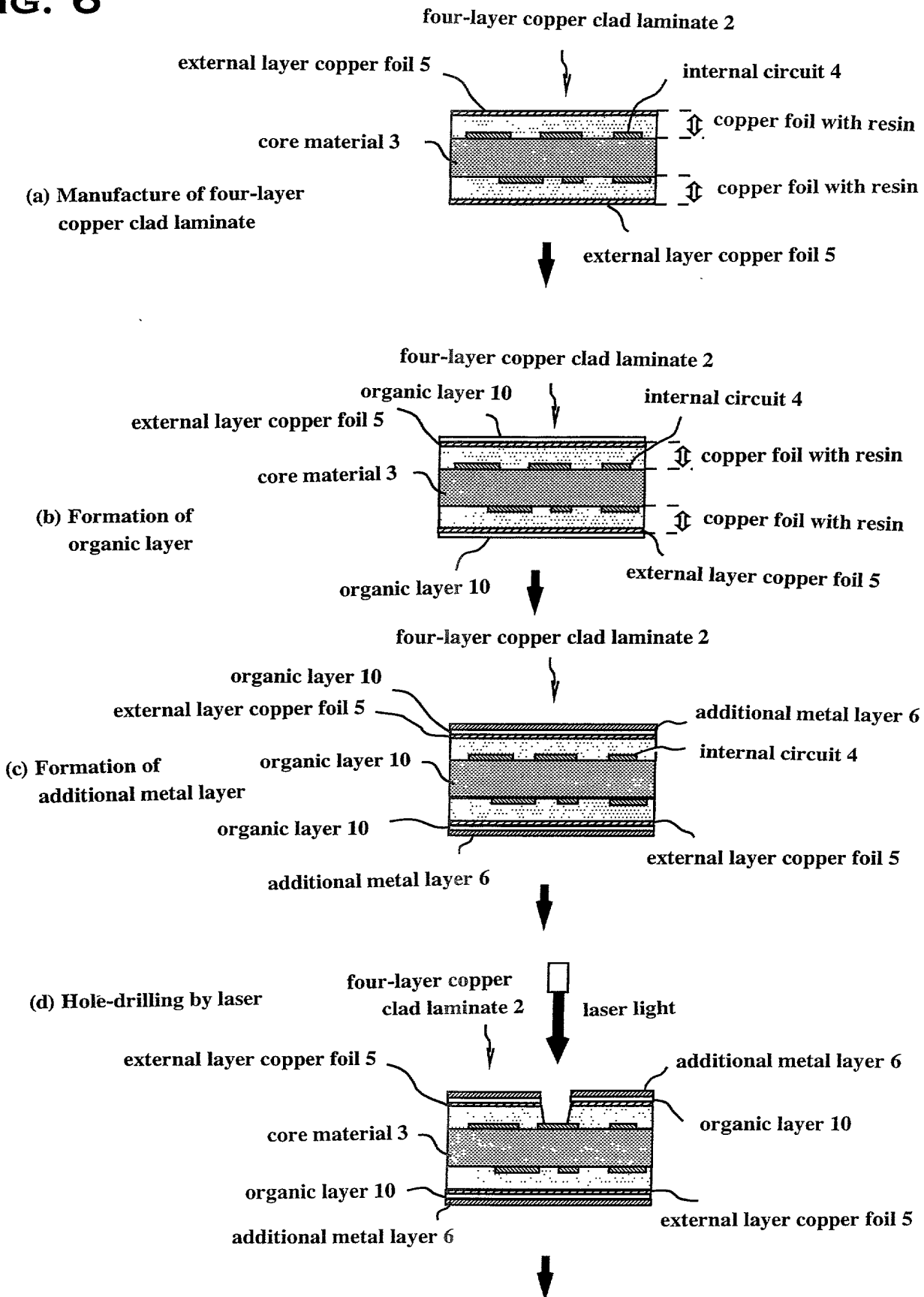


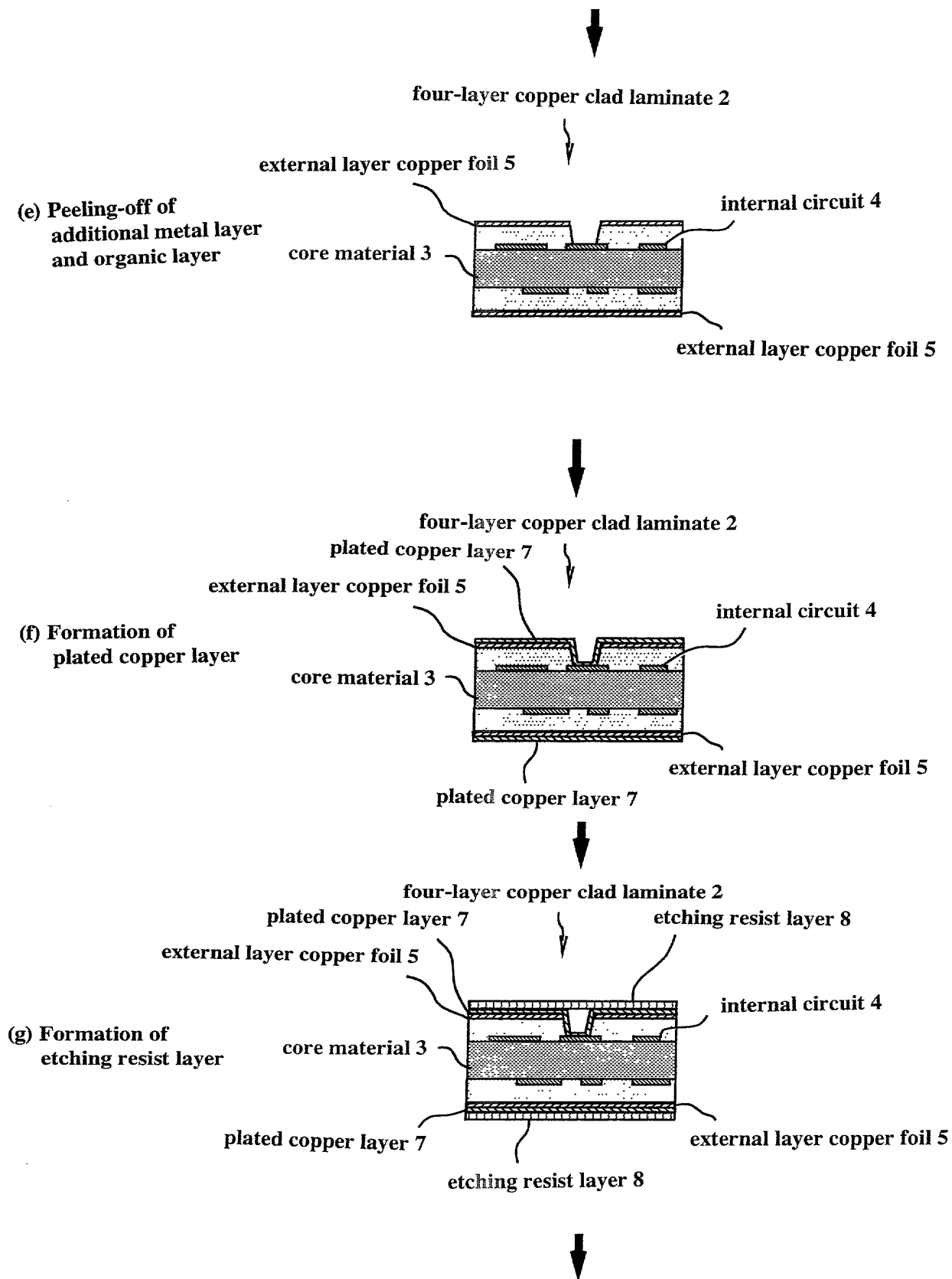
FIG. 5



**FIG. 6**

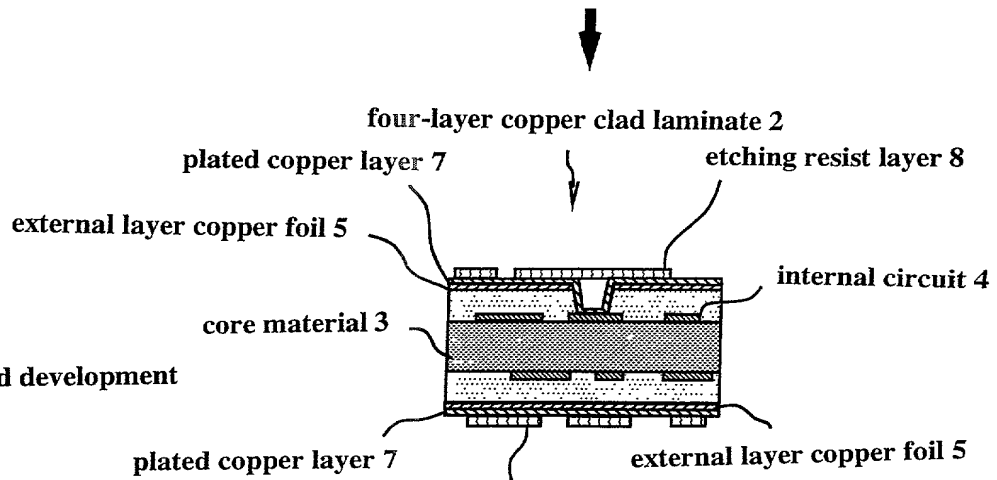


**FIG. 7**

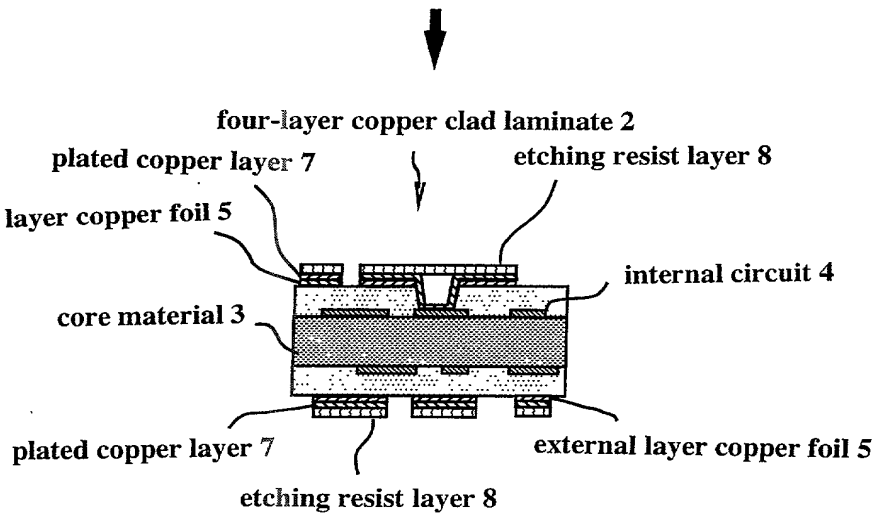


**FIG. 8**

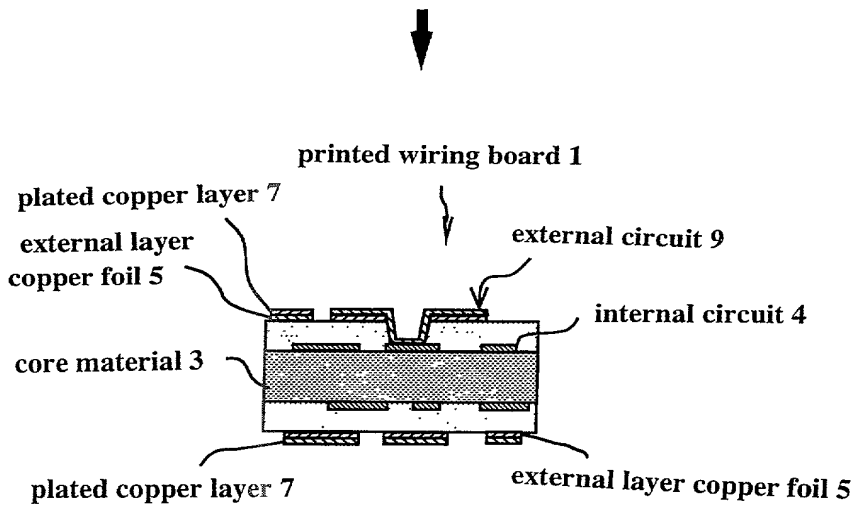
(h) Exposure and development



(i) Formation of a circuit through etching

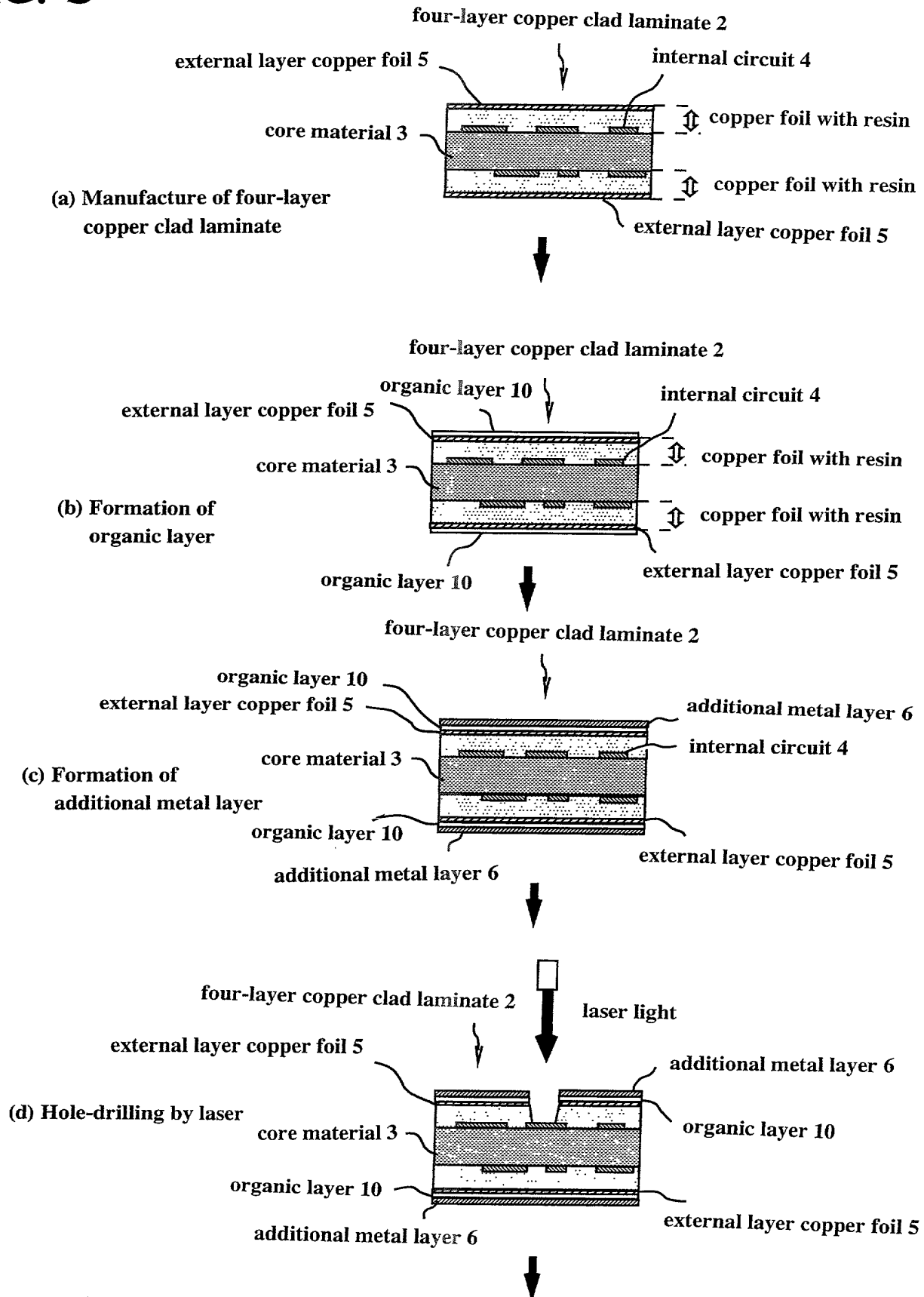


(j) Peeling-off of etching resist layer





**FIG. 9**



**FIG. 10**

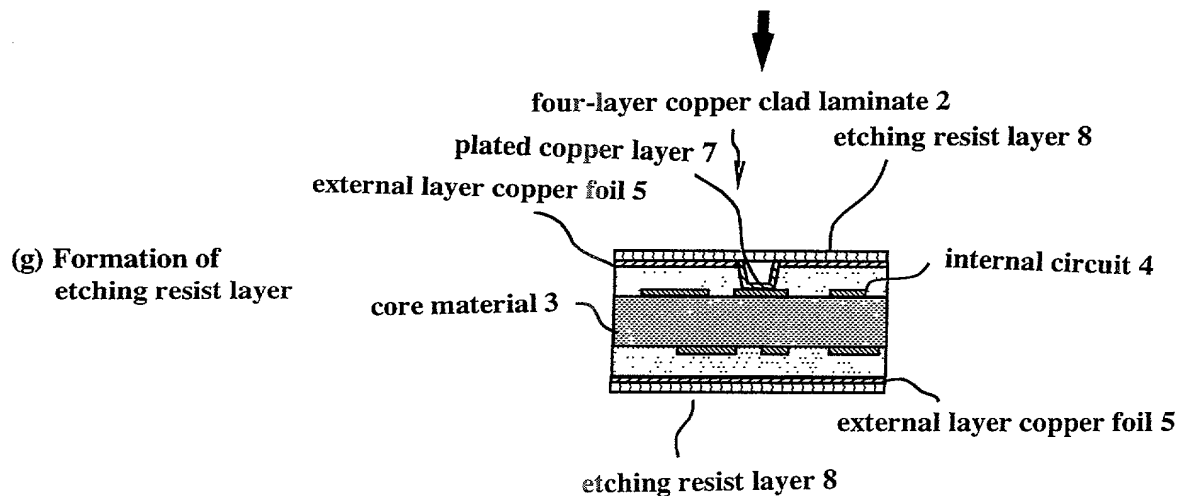
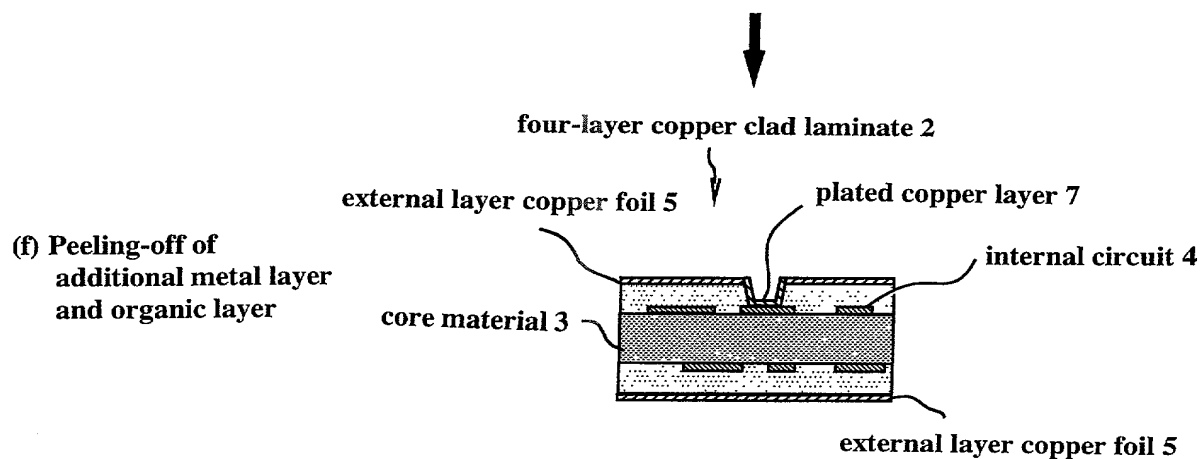
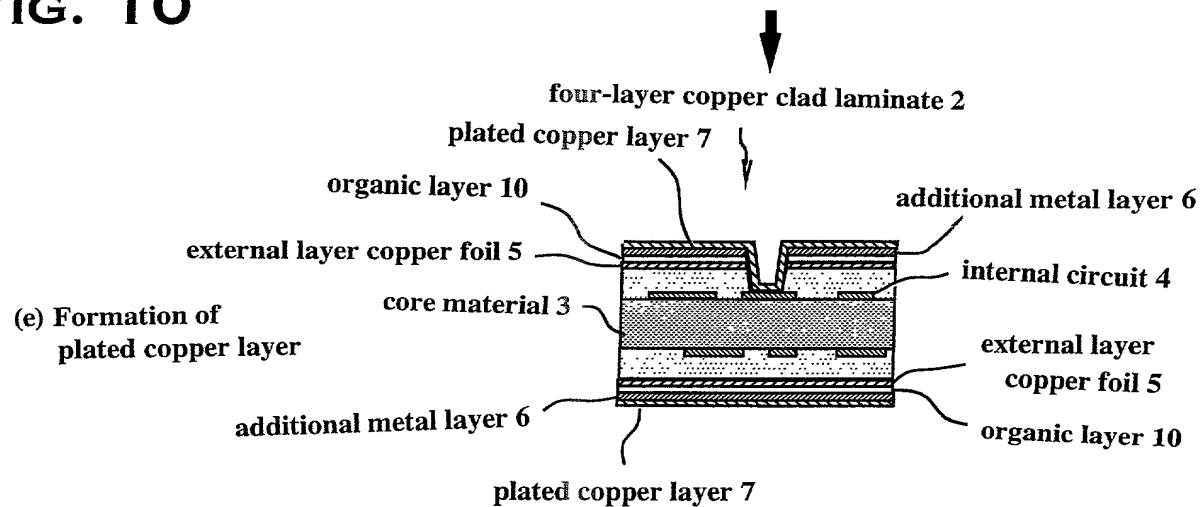


FIG. 11

